

The Physics and Technology of Amorphous SiO₂

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By Roderick A B Devine

Springer-Verlag New York Inc., United States, 2011. Paperback. Book Condition: New. 244 x 168 mm. Language: English . Brand New Book ***** Print on Demand *****. The contents of this volume represent most of the papers presented either orally or as posters at the international conference held in Les Arcs, Savoie, from June 29 to July 3 1987. The declared objective of the conference was to bring together specialists working in various fields, both academic and applied, to examine the state of our understanding of the physics of amorphous silicon from the point of view of its structure, defects (both intrinsic and extrinsic), its ability to transport current and to trap charges, its sensitivity to irradiation, etc. For this reason, the proceedings is divided, as was the conference schedule, into a number of sections starting from a rather academic viewpoint of the internal structure of idealized SiO₂ and progressing towards subjects of increasing technological importance such as charge transport and trapping and breakdown in thin films. The proceedings terminates with a section on novel applications of amorphous SiO₂ and in particular, buried oxide layers formed by ion implantation. Although every effort was made at the conference...



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